

Title (en)

POLISHING PAD HAVING A TRICOT MESH FABRIC AS A BASE

Title (de)

POLIERTUCH MIT TRIKOTNETZFASERN ALS BASIS

Title (fr)

TAMPON À POLIR PRÉSENTANT UN TISSU À MAILLES TRICOTÉ COMME BASE

Publication

EP 2340915 A2 20110706 (EN)

Application

EP 09819329 A 20090910

Priority

- KR 2009005130 W 20090910
- KR 20080013538 A 20081010

Abstract (en)

Disclosed herein is a polishing pad having a substrate woven in a network form, capable of adsorbing dust generated during polishing of an object into meshes formed in the substrate to discharge the adsorbed dust to an external dust suction system or receive the dust in the meshes in a pocket form, in turn improving polishing efficiency of the polishing pad. In addition, polishing yarns are solidly adhered to a face part with relatively wider area on one side of the substrate so as to enhance durability of the pad. The polishing pad according to an exemplary embodiment includes a tricot mesh fabric 10 having a flat face part 12 formed by densely weaving fiber yarns in a network form, as well as meshes 14 formed between such flat face parts 12, a polishing yarn layer 20 having polishing yarns adhered to the flat face part on one side of the tricot mesh fabric 10 by an adhesive, and a top layer 30 consisting of a Velcro fabric attached to the other side of the tricot mesh fabric 10, so as to detachably combine the polishing pad with a hook type male Velcro component formed on a surface of a polishing pad holder mounted on a power tool (such as a sander).

IPC 8 full level

B24D 3/20 (2006.01)

CPC (source: EP)

B24D 11/02 (2013.01); **B24D 13/147** (2013.01)

Citation (search report)

See references of WO 2010041822A2

Cited by

DE102016118648B4

Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO SE SI SK SM TR

Designated extension state (EPC)

AL BA RS

DOCDB simple family (publication)

EP 2340915 A2 20110706

DOCDB simple family (application)

EP 09819329 A 20090910